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Front Matter: Volume 8105

, "Front Matter: Volume 8105," Proc. SPIE 8105, Instrumentation, Metrology, and Standards for Nanomanufacturing, Optics, and Semiconductors V, 810501 (26 September 2011); doi: 10.1117/12.906478

SPIE.

Event: SPIE NanoScience + Engineering, 2011, San Diego, California, United States

PROCEEDINGS OF SPIE

Instrumentation, Metrology, and Standards for Nanomanufacturing, Optics, and Semiconductors V

**Michael T. Postek
Victoria A. Coleman**
Editors

**24–25 August 2011
San Diego, California, United States**

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Published by
SPIE

Volume 8105

Proceedings of SPIE, 0277-786X, v. 8105

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Author(s), "Title of Paper," in *Instrumentation, Metrology, and Standards for Nanomanufacturing, Optics, and Semiconductors V*, edited by Michael T. Postek, Victoria A. Coleman, Proceedings of SPIE Vol. 8105 (SPIE, Bellingham, WA, 2011) Article CID Number.

ISSN 0277-786X

ISBN 9780819487155

Published by

SPIE

P.O. Box 10, Bellingham, Washington 98227-0010 USA

Telephone +1 360 676 3290 (Pacific Time) · Fax +1 360 647 1445

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